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|--|---|----------------------|---------------------------------------|---------------------------------|
| LPCVD | Tube 3 | Material | UnDoped Poly Silicon Amorphous | |
| Uniformity: | Film Uniformity Variance < 2% across 3" wafer | | | |
| Gases | Flow Rate | Time(minutes) | Film Thickness(nm) | Deposition rate (nm/min) |
| Temperature | 550 C | 10 | 14.75 | 1.48 |
| Comments: 30 minutes trial was on 4" wafer, other trials on 3" wafer | | 20 | 38.32 | 1.92 |
| | | 30 | 54.5 | 1.82 |
| | | 40 | 69.31 | 1.73 |
| | | 50 | 90.52 | 1.81 |
| | | 60 | 110.94 | 1.85 |

